CONTENTS

Introduction . . . . . **ix**
H. V. Boenig, U.S.A.
Applications of Low-Temperature Plasma Technology **1**
H. V. Boenig, U.S.A.
Investigation of the Oxidation Process and the Properties of Ultrathin SiO_2 Obtained in RF Oxygen Plasma **11**
E. D. Atanassova, Bulgaria
Oxidation Processes in Plasmas **29**
P. Friedel and S. Gourier, France; *Summary by H. V. Boenig, U.S.A.*
Metal Doped Polymer Films Prepared in Low Pressure Reactive Plasmas **37**
H. Biederman and L. Martinů, Czechoslovakia
Fabrication of Membranes for Reverse Osmosis **49**
K. Czeija, Austria
Metal Nitride Film Formation in Plasmas **53**
O. Matsumoto, Japan
Plasma-Polymerized Films Sensitive to Moisture **80**
N. Inagaki, Japan
Microlenses Prepared by the Plasma-Activated Chemical Vapor Deposition Technique **92**
K. Kuppers and K. H. Schelhas, Germany; U. Biermann, G. D. Khoe, and H. G. Kock, The Netherlands
Recent Research into the Erosion of Non-Refractory Cathodes in Arc Plasma Devices **108**
A. E. Guile, England

Plasma-Hydrogenation Effects in Amorphous and Polycrystalline Silicon Films 138
S. Hasegawa, Japan
Advances in Plasma Deposition of Thin Films: Review I. Plasma Chemical Vapor Deposition of Organic Thin Films . . . 153
H. V. Boenig, U.S.A.
II. Plasma Chemical Vapor Deposition of Inorganic Thin Films 195
H. V. Boenig, U.S.A.
Electron Energy Distribution Functions in Thin Film Deposition Plasmas 245
A. Garscadden, U.S.A.
Kinetics of the Methane Conversion in a Glow Discharge Up to Chemical Equilibrium 251
R. Mach and H. Drost, Germany
Advances in Basic and Applied Aspects of Microwave Plasma Polymerization 257
M. R. Wertheimer, J. E. Klemberg-Sapieha, and H. P. Schreiber, Canada
Metal Clusters in Plasma Polymerized Matrices. Part I: Gold 263
E. Kay, U.S.A. and M. Hecq, Belgium
Controlling the Chemistry of a Plasma Deposited Coating for an Application to Videodiscs 273
D. L. Matthies and G. Kaganowicz, U.S.A.
Plasma Polymerized Ethane in a Capacitively Coupled Reactor . . . 279
A. T. Bell, U.S.A.; S. Morita, M. Shen, S. Ishibashi, K. Hida, H. Kawamura, and S. Ikeda, Japan
Plasma Polymerized High Energy Density Dielectric Films 286
F. G. Yamagishi and L. J. Miller, U.S.A.
Plasma-Polymerized Phenyl Isothiocyanate Films—Structure and Properties 293
G. Czeremuszkin, A. M. Wróbel, and M. Kryszewski, Poland
Radical and Ion-Molecule Reactions in a Microwave Plasma at Low Pressures 299
R. Avni, U.S.A.; U. Carmi, I. Rosenthal, and A. Inspektor, Israel
Recent Development in Plasma Polymerized Dry Developable Electron Beam Resist 311
S. Hattori, J. Tamano, M. Ieda, and S. Morita, Japan
Surface Fluorination of Polymers in a Glow Discharge Plasma: Photochemistry 317
R. E. Cohen, R. F. Baddour, and G. A. Corbin, U.S.A.
Effect of Ethylene on RF Plasma Decomposition and Polymerization of Ethane in a Flow Low Pressure System 322
P. Canepa, G. Castello, and M. Nicchia, Italy
Polymerization of a Cyclic Fluorocarbon Monomer in Low Pressure RF and MW-Plasmas 326
J. Kammermaier, G. Rittmayer, and R. Schulte, Federal Republic of Germany

RF Sputtering of Polyimide 332
M. Kitoh, Y. Honda, and Y. Kokaku, Japan
Some Studies on Coating of Activated Charcoal with Plasma Polymer Hexamethyldisiloxane 339
N. Hasirci and C. Akovali, Turkey
New Polymeric Structures Synthesized Under Cold Plasma Conditions 343
C. I. Simionescu, F. Dénes, and M. Totolin, Romania
Surface Treatment of Silicon by Plasma Polymerization of Different Organic Gases 344
F. Arefi, J. Amouroux, and M. Goldman, France
Plasma Technology in Integrated Optics: Optical Wave Guides 350
H. V. Boenig, U.S.A.
Reactions of Aromatic Compounds with Oxygen in a Radiofrequency Discharge 365
M. Tezuka, T. Yajima, and A. Tsuchiya, Japan